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Notice of Allowability	Application No.	Applicant(s)
	10/750,522	GARDNER, DONALD S.
	Examiner	Art Unit
	Hsien-ming Lee	2823
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS nerewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT F of the Office or upon petition by the applicant. See 37 CFR 1.31	S (OR REMAINS) CLOSED in this ap b) or other appropriate communication RIGHTS. This application is subject	oplication. If not included n will be mailed in due course. THIS
1. \square This communication is responsive to <u>4/2/2007</u> .		
2. ☑ The allowed claim(s) is/are <u>2-15 and 32-36</u> .	•	•
 Acknowledgment is made of a claim for foreign priority to a) ☐ All b) ☐ Some* c) ☐ None of the: 1. ☐ Certified copies of the priority documents have 	/e been received.	
2. Certified copies of the priority documents have	• • • • • • • • • • • • • • • • • • • •	
3. Copies of the certified copies of the priority d	ocuments have been received in this	national stage application from the
International Bureau (PCT Rule 17.2(a)).		
* Certified copies not received:		
Applicant has THREE MONTHS FROM THE "MAILING DATE noted below. Failure to timely comply will result in ABANDON THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		complying with the requirements
4. A SUBSTITUTE OATH OR DECLARATION must be subr INFORMAL PATENT APPLICATION (PTO-152) which give		
5. CORRECTED DRAWINGS (as "replacement sheets") mu	ust be submitted.	
(a) ☐ including changes required by the Notice of Draftsper 1) ☐ hereto or 2) ☐ to Paper No./Mail Date	rson's Patent Drawing Review (PTO	-948) attached
(b) ☐ including changes required by the attached Examiner Paper No./Mail Date	_	Office action of
Identifying indicia such as the application number (see 37 CFR each sheet. Replacement sheet(s) should be labeled as such in		
 DEPOSIT OF and/or INFORMATION about the dependence of the dependence of	osit of BIOLOGICAL MATERIAL	must be submitted. Note the
· · · · · · · · · · · · · · · · · · ·		
Attachment(s)		
1. Notice of References Cited (PTO-892)	5. Notice of Informal I	* *
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6. ☐ Interview Summary Paper No./Mail Da	/ (PTO-413),
3. Information Disclosure Statements (PTO/SB/08), Paper No./Mail Date	7. Examiner's Amend	ment/Comment
4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	8. 🛭 Examiner's Statem	ent of Reasons for Allowance
	9.	
		HSIEN-MING LED PRIMARY EXAMINED

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DETAILED ACTION

Remarks

1. The objection and rejection, as set forth in the previous office action, have been withdrawn in response to applicant's amendment filed 4/2/2007.

Examiner's Amendment

2. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Philip A. Pedigo (Reg. No. 52,107) on June 7, 2007.

3. The application has been amended as follows:

Cancel non-elected claims 16-30.

In claim 10, line 3, delete "first" before "strained."

In claim 11, line 2, delete "first" before "strained."

In claim 33 (line 1), claim 34 (line 1), claim 35 (line 1) and claim 36 (line 1), replace "system" with -- integrated circuit --.

Allowable Subject Matter

- 4. Claims 2-15 and 32-36 are allowed.
- 5. The following is an examiner's statement of reasons for allowance:

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In re claim 2, the primary reason for allowance of the claim is the patentably distinct features comprising an optically active layer formed on an upper surface of the substrate, the optically active layer including a layer of SiGe having a quantum well and comprising a layer of SiGe *nanocrystals*.

In re claim 32, the primary reason for allowance of the claim is the patentably distinct features comprising an optically active layer formed on the semiconductor substrate, the optically active layer including a strained layer of SiGe having a quantum well and the strained layer of SiGe is *doped with at least one of arsenic, phosphorus and antimony*.

None of the prior art of record, either alone or combination, teaches or suggests the foregoing limitations. The present application is thus allowed.

- 6. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."
- 7. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Hsien-ming Lee whose telephone number is 571-272-1863. The examiner can normally be reached on Tuesday-Thursday $(7:30 \sim 6:00)$.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Matthew Smith can be reached on 571-272-1907. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Hsien-ming Lee Primary Examiner Art Unit 2823

June 7, 2007

HSIEN-MING LEE